

Fig. 2

BK 12/19

312/11 REC 1151

1. The present invention relates to a method of forming a thin film on a substrate. The method includes the steps of: (a) providing a substrate; (b) depositing a thin film on the substrate; (c) patterning the thin film; and (d) etching the substrate.

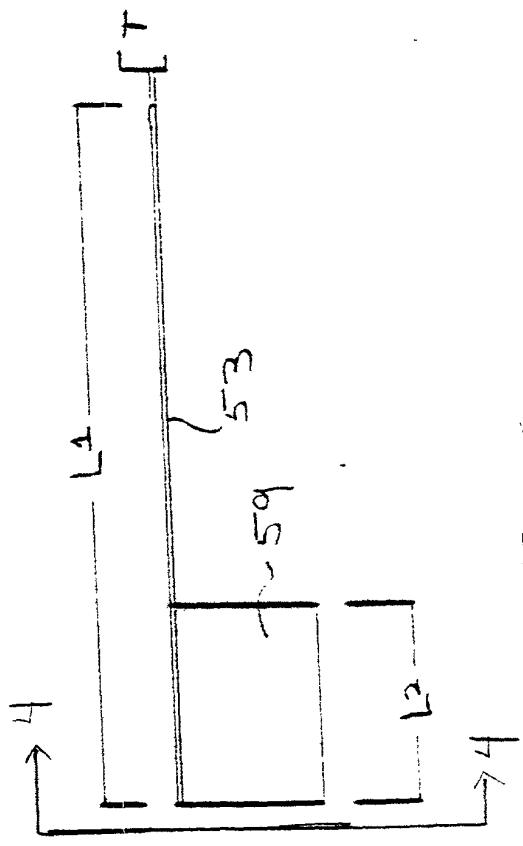


Fig 3

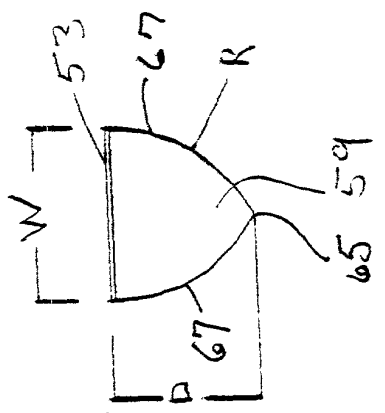


Fig 4